

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1767	(438/687).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/08/17 17:02
L2	2	1 and sidewall with photosensitive	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 17:03
L3	1	soak\$3 with photosensitive with (sidewall side\$3wall)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 17:05
L4	1	soak\$3 with (benzocyclobutane BCB photosensitive polyimide) with (sidewall side\$3wall)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 17:06
L5	11	(absorb assimilate bathe, damp\$3 dip\$3 drench\$3 dr immerg\$3 immers\$3 impregnat\$3, infiltrat\$3 infus\$3 penetrat\$3 saturat\$3) with (benzocyclobutane BCB photosensitive polyimide) with (sidewall side\$3wall)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 17:14
L6	0	(absorb assimilate bathe, damp\$3 dip\$3 drench\$3 dr immerg\$3 immers\$3 impregnat\$3, infiltrat\$3 infus\$3 penetrat\$3 saturat\$3) with photosensitive with (sidewall side\$3wall)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 17:14
L7	6	(absorb assimilate bathe, damp\$3 dip\$3 drench\$3 dr immerg\$3 immers\$3 impregnat\$3, infiltrat\$3 infus\$3 penetrat\$3 saturat\$3) with photosensitive with (sidewall side\$3wall)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 17:16
L8	7	(absorb assimilate bath\$3, damp\$3 dip\$3 drench\$3 dr immerg\$3 immers\$3 impregnat\$3, infiltrat\$3 infus\$3 penetrat\$3 saturat\$3) with photosensitive with (sidewall side\$3wall)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 17:35

EAST Search History

L9	1	8 not 7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 17:35
L10	945	(438/629).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/08/17 17:35
L11	0	10 and (absorb\$3 assimilate bath\$3, damp\$3 dip\$3 drench\$3 dr immerg\$3 immers\$3 impregnate\$3, infiltrate\$3 infuse\$3 penetrate\$3 saturate\$3) with photosensitive with (sidewall side\$3wall)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 17:35
L12	0	10 and (absorb\$3 assimilate\$3 bath\$3, damp\$3 dip\$3 drench\$3 dr immerg\$3 immers\$3 impregnate\$3, infiltrate\$3 infuse\$3 penetrate\$3 saturate\$3) with photosensitive with (sidewall side\$3wall)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 17:36
L13	1	10 and (soak\$3 absorb\$3 assimilate\$3 bath\$3, damp\$3 dip\$3 drench\$3 dr immerg\$3 immers\$3 impregnate\$3, infiltrate\$3 infuse\$3 penetrate\$3 saturate\$3) with photosensitive with (sidewall side\$3wall)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 17:36
L14	12	("6482733" "6518168" "6528409" "6585811" "6586334" "6689686").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L15	2	"20050127515".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L16	3145	(257/e21.576).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/08/17 18:38
L17	0	L14 and sidewall with photosensitive	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38

EAST Search History

L18	6	L16 and sidewall with photosensitive	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L19	40	L16 and sidewall with treatment	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L20	12	L16 and sidewall with prevent with copper	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L21	28	L16 and sidewall with prevent\$3 with copper	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L22	0	L16 and sidewall with liner with (benzocyclobutane BCB photosensitive polyimide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L23	2	L16 and sidewall with barrier with (benzocyclobutane BCB photosensitive polyimide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L24	0	L16 and sidewall with prevent\$3 with (benzocyclobutane BCB photosensitive polyimide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L25	10512	(257/e21.57\$1).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/08/17 18:38
L26	41	L25 and sidewall with (barrier cap\$3 lin\$3 coat\$3 film layer prevent\$3) with (benzocyclobutane BCB photosensitive polyimide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38

EAST Search History

L27	41	L26 not L21	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L28	7	("5141817" "5955528" "5962113" "6162838" "6319854" "6380346").PN. OR ("6903006"). URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/08/17 18:38
L29	36	("4789648" "4837123" "4921723" "5081060" "5100838" "5106780" "5118382" "5144411" "5286674" "5525552" "5663101").PN. OR ("5759911").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/08/17 18:38
L30	4	L16 and sidewall with photomask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L31	30	L25 and sidewall with porous with surface	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L32	21	("20010051420" "20020055256" "20 030001282" "20030143839" "61805 18" "6482733" "6518166" "6528409" "6585811" "6586334" "6689686"). PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L33	2	"6541842".PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L34	5	("5103285" "5818071" "6231989").PN. OR ("6541842"). URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/08/17 18:38
L35	2	("2002/0055256").URPN.	USPAT	OR	ON	2006/08/17 18:38
L36	1	"6586334".pn.	USPAT	OR	ON	2006/08/17 18:38
L37	7	("20010019884" "6217721" "6319822" "6326297" "6380628"). PN. OR ("6586334").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/08/17 18:38
L38	55	L25 and pore near2 seal\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38

EAST Search History

L39	80	L25 and (pores porous) near2 seal\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L40	88	(pores porous) near2 seal\$4 same (benzocyclobutane BCB photosensitive polyimide photo near2 resist photo near2 mask)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L41	1311	(257/762).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/08/17 18:38
L42	1	L41 and (pores porous) near2 seal\$4 and (benzocyclobutane BCB photosensitive polyimide photo near2 resist photo near2 mask)with (seal\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L43	13	L41 and (pores porous) near2 seal\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L44	504	(257/767).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/08/17 18:38
L45	2	L44 and (pores porous) near2 seal\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L46	2	"5412868".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L47	12	("6482733" "6518168" "6528409" "6585811" "6586334" "6689686").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38

EAST Search History

L48	924	silicon near2 oxide with photosensitive	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L49	0	silicon near2 oxide with photosensitive same pore with (seal\$5)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L50	31	silicon near2 oxide with photosensitive with polyimide with BCB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L51	197138	silicon near2 oxide (photomask photoresist photosensitive polyimide BCB)with selant	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L52	0	silicon near2 oxide with (photomask photoresist photosensitive polyimide BCB)with selant	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L53	0	silicon near2 oxide with (photomask photoresist photosensitive polyimide BCB) with selant	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L54	43	silicon near2 oxide with (photomask photoresist photosensitive polyimide BCB) with seal\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L55	106	(silicon near2 oxide "SiO.sub.2")with (photomask photoresist photosensitive polyimide BCB) with seal\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L56	63	L55 not L54	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38

EAST Search History

L57	13	(silicon near2 oxide "SiO.sub.2")with (photomask photoresist photosensitive polyimide BCB) near4 seal\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L58	1639	(photomask photoresist photosensitive BCB) near4 seal\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L59	9	(photomask photoresist photosensitive BCB) near4 seal\$3 and (pores porous) with via	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L60	1220	(silicon near2 oxide "SiO.sub.2")with BCB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L61	3	(silicon near2 oxide "SiO.sub.2")with BCB with seal\$5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L62	35	("siO.sub.2" silicon near2 oxide) with photosensitive with polyimide with BCB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L63	1	benzocyclobutene near2 sealant	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L64	3	benzocyclobutene near2 seal\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L65	22	benzocyclobutene near2 low with k	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38

EAST Search History

L66	6036	photomask with materials	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L67	3	photomask with materials same sealant	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L68	287	(pores pore) and seal\$4 and via	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L69	30	(pores pore) and seal\$4 and via with hole	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L70	2623	(257/774).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/08/17 18:38
L71	0	L70 and (pores pore) and seal\$4	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L72	10	L70 and (pores pore) with seal\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L73	24	L70 and (pores pore) and seal\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L74	6	("5243222" "6229211" "6677678").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L75	12	("4659205" "5477057" "5550007" "5824599" "5882999" "5906911" "5910453" "5933761" "6121156" "6225217" "6323076" "6355555").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/08/17 18:38

EAST Search History

L76	16	("3622382" "4465705" "4789648" "4925805" "4968636" "5091763" "5314843" "5316965" "5324680" "5429955" "5578523" "5672531" "5677224" "5712185" "5741626" "5796133").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/08/17 18:38
L77	0	"64445557".pn.	US-PGPUB; USPAT; USOCR	OR	ON	2006/08/17 18:38
L78	2	"6444557".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L79	2	"20050127515".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L80	340	dielectric with constant with (silica adj aerogel MSQ)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L81	2	"5741626".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L82	5	photoresist with (photosensitive near1 polyimide BCB)same (silsequioxane MSQ silica near1 aerogel)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L83	671	photoresist with (photosensitive near1 polyimide BCB)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L84	5	photoresist with (photosensitive near1 polyimide and BCB)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38

EAST Search History

L85	2	photoresist with spin with coating with MSQ	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L86	0	(photo near1 resist photo near1 mask) with spin with coating with MSQ	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L87	2	(photo\$2resist photo\$2mask) with spin with coating with MSQ	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L88	8	photomask with BCB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L89	324624	photresist wit made with BCB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L90	0	photresist with made with BCB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L91	28	photoresist with made with BCB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L92	0	"photoresit" near2 made	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L93	16	photoresit with material	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38

EAST Search History

L94	1	photoresit with BCB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L95	0	photoresit with orgnic	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L96	9	photoresit with organic	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L97	0	photoresit with photosensitive adj polyimide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L98	0	photoresit with photosensitive adj polyimide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L99	466	resist with photosensitive adj polyimide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L100	42	resist with (BCB photosensitive adj polyimide) and damascene	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L101	60	resist with (BCB photosensitive adj polyimide) and interconnect and "257"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38

EAST Search History

L102	24	(US-20050173804-\$ or US-20010051420-\$ or US-20030143839-\$ or US-20030001282-\$ or US-20020055256-\$ or US-20050048765-\$ or US-20030134508-\$ or US-20010054769-\$ or US-20050133920-\$ or US-20050127515-\$ or US-20050003594-\$ or US-20040256618-\$ or US-20020182851-\$ or US-20020016070-\$).did. or (US-6903006-\$ or US-4832788-\$ or US-5759911-\$ or US-6541842-\$ or US-6586334-\$ or US-6528409-\$ or US-6482733-\$ or US-6180518-\$ or US-4661697-\$ or US-5741626-\$ or US-6486057-\$ or US-6593220-\$). did. or (DE-10014587-\$).did. or (JP-04158557-\$).did.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2006/08/17 18:38
L103	0	L102 and soak\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38
L104	2	"20010054769".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/17 18:38